

**RESPONSE UNDER 37. CFR 1.116
EXPEDITED PROCEDURE
EXAMINING GROUP 1752**

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of

Hiroshi TAKANASHI et al.

Serial No. 09/262,077

Filed March 4, 1999



Docket No.01497/FP/TOK-16-US/YH

Group Art Unit 1752

Examiner S. Lee

8/11/01

NEGATIVE-WORKING PHOTOSENSITIVE :
RESIN COMPOSITION AND PHOTOLEN- :
SITIVE RESIN PLATE USING THE SAME :

THE COMMISSIONER IS AUTHORIZED
TO CHARGE ANY DEFICIENCY IN THE
FEE FOR THIS PAPER TO DEPOSIT
ACCOUNT NO. 23-0975.

RESPONSE TO FINAL REJECTION

Assistant Commissioner for Patents,
Washington, D.C.

Sir:

This is in response to the Final Rejection dated January 3, 2000, the period for response having been extended for two months by the attached petition.

REMARKS

Favorable reconsideration is respectfully requested.

The claims are 6 to 9.

Claims 6 to 9 have been rejected under 35 U.S.C. 103 as being unpatentable over Pine (US 4,361,640).

This rejection is respectfully traversed.

In the rejection, it is asserted that the recited range of 0 to 18% by weight for the amount of o,p-toluene sulfonamide taught by Pine encompasses the presently claimed range 0.001 - 0.3 wt% of component (E), and that the applicant did not show the criticality of the presently claimed range.

In reply, applicants performed experiments to show the criticality of the claimed range of 0.001 - 0.3 wt% of component (E) by using N-ethyltoluenesulfonamide, which is considered to

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